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**(54) PRODUCTION OF EXTREMELY THIN
PHOTOSENSITIVE FILM**

(57) Abstract:

PURPOSE: To provide a method of producing an extremely thin photosensitive film in which when coating a support body film with a photosensitive resin composition solution, the coating is effectively performed without color irregularity, vertical streaks lateral streaks or the like

CONSTITUTION: In a method of producing an extremely

thin photosensitive film in which a photosensitive resin composition solution where a photosensitive resin composition is dissolved in an organic solvent is applied to a film support body and is dried to form an extremely thin photosensitive resin composition layer of 0.5-5 μ m, a contact angle when the photosensitive resin composition solution is applied to the film support body is made 12-20°.

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